

### **Complete Listing of Claims**

1.-7. (Cancelled)

8. (Original) A method for manufacturing a glass substrate of an information recording medium by polishing a surface of a glass workpiece with a polishing pad,

wherein polishing includes a first polishing step for subjecting a surface of the glass workpiece to rough polishing, and a second polishing step for subjecting the surface of the glass workpiece to precision polishing so that the surface is further smoothed,

wherein the polishing pad is used in a second polishing step.

9. (Original) The method according to claim 8, wherein the number of pores on the polishing pad is 400 to 10,000 in 1 mm<sup>2</sup>.

10. (Original) The method according to claim 8, wherein the compression deformation amount of the polishing pad is 40 to 60 μm.

11. (Original) The method according to claim 8, wherein the opening sizes of the pores are 10 to 60 μm.

12. (Original) The method according to claim 8, wherein the glass workpiece is one of a plurality of glass workpieces that are simultaneously polished, wherein the variation of the thickness of removal layers of the glass workpieces is equal to or less than 0.2 μm.

13. (Original) A glass substrate of an information recording medium, manufactured by the method according to claim 8,

wherein, when measured with a three-dimensional external structure analysis microscope at a wavelength ( $\lambda$ ) of 0.2 to 1.4 μm, the height (NRa) of micro-waviness on the surface is equal to or less than 0.15 nm.

14. (Cancelled)